Fast-writing E-beam for large arrays of nano-holes

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Fast-writing E-beam for large arrays of nano-holes

Emil Højlund-Nielsen\textsuperscript{a}, Jeppe Clausen\textsuperscript{b}, Alexander Bruun Christiansen\textsuperscript{a}, Tine Greibe\textsuperscript{c}, N. Asger Mortensen\textsuperscript{b}, Anders Kristensen\textsuperscript{a}

\textsuperscript{a}DTU Nanotech, Oersteds Plads Bygning 345b 2800 Kongens Lyngby, Denmark
\textsuperscript{b}DTU Fotonik, Oersteds Plads Bygning 343, 2800 Kongens Lyngby, Denmark
\textsuperscript{c}DTU Danchip, Oersteds Plads Bygning 347, 2800 Kongens Lyngby, Denmark
E-mail: emiho@nanotech.dtu.dk

Efficient nanoscale patterning of large areas is required for sub-wavelength optics. Here we use a fast-writing strategy described in [1], where electron beam lithography (EBL) with a focused Gaussian beam is used to define shapes directly. The serial technique is optimized for speed and pattern fidelity to a maximum writing speed of around 30 min/cm\textsuperscript{2} for 200 nm periods in 2D lattices. The overall costs in terms of machine time and feasibility are assessed.

**Validation and Experimental Results**

The JEOL JBX-9500FS is a prototype EBL 100 keV system with electron-beam scanning speeds up to 100 MHz. Writing time tests of exposing 5 mm x 5 mm can be seen in Fig. 5 as function of dose. The effective current, that is the inverse slope is 28.0 nA, including time for calibration etc. Writing times are below 2 h/cm\textsuperscript{2} and even a writing time of around 30 min/cm\textsuperscript{2} for 200 nm periods in 2D lattices can be achieved. Efficient calibration routines become imperative with this method.

**Conclusion**

An EBL writing time below two hours per cm\textsuperscript{2} provides new possibilities where sub-wavelength structures can be used to provide functionality such as anti-reflective or plasmonic effects for large area applications in a cost-effective manner, similar to traditional parallel processing techniques.

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**References**